

## Supplementary Information

### A study of the doping process in $\text{Li}_4\text{Ti}_5\text{O}_{12}$ and $\text{TiO}_2$ battery electrode materials studied in ion-gated transistor configuration

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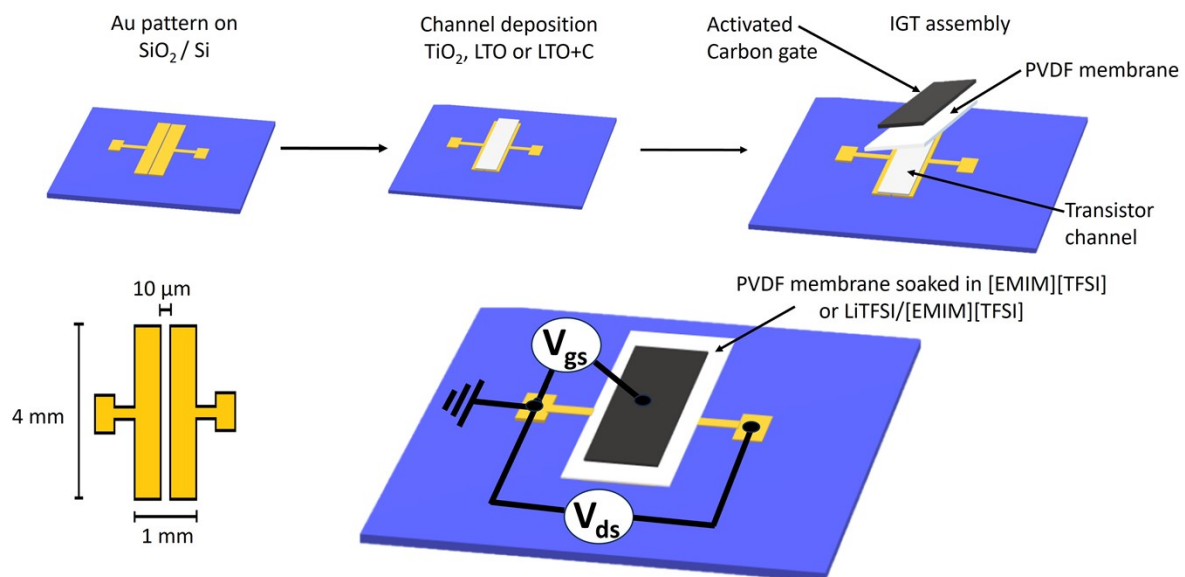
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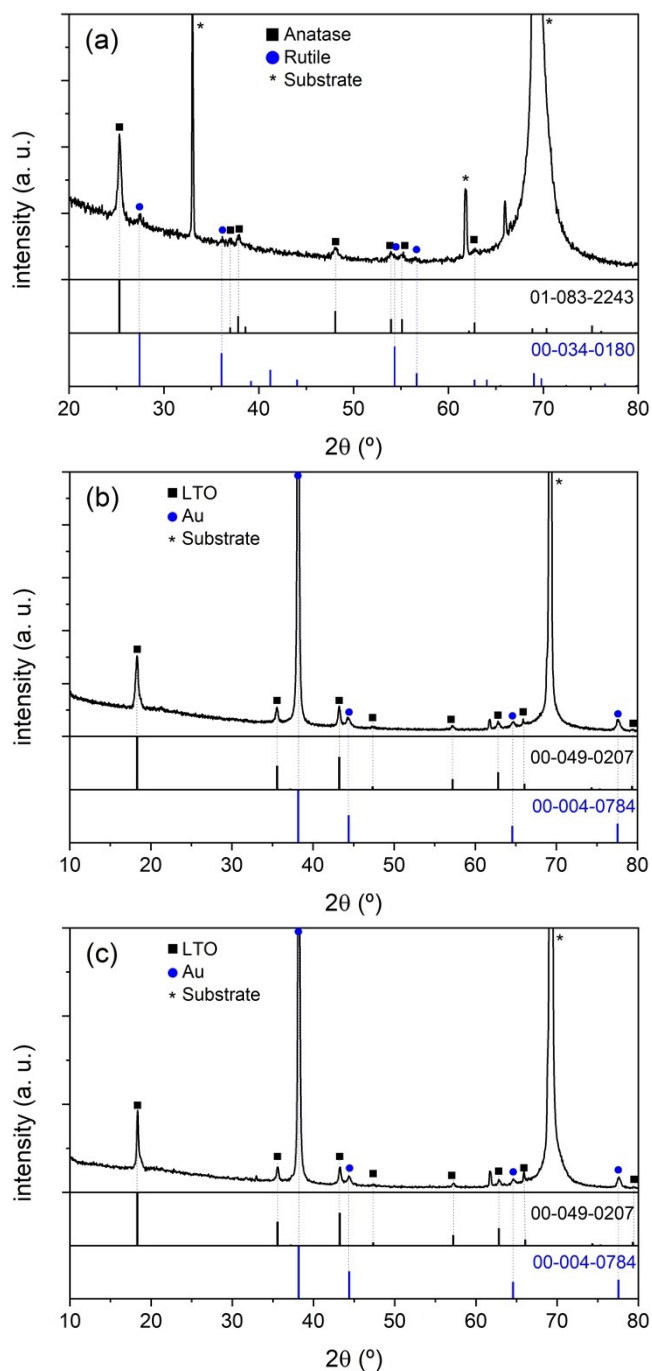
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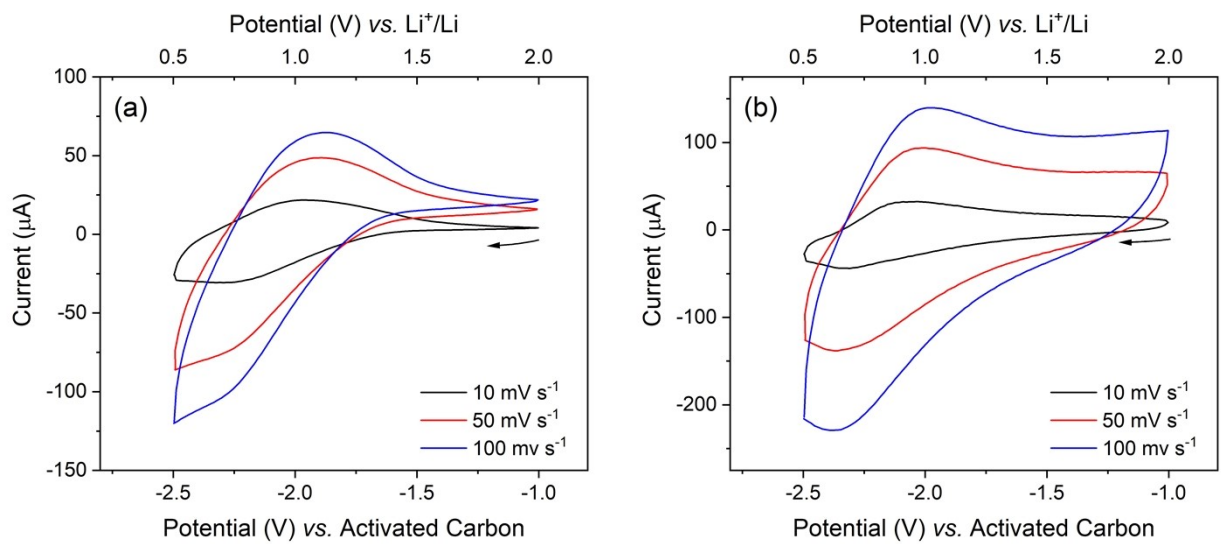
#These authors equally contributed.



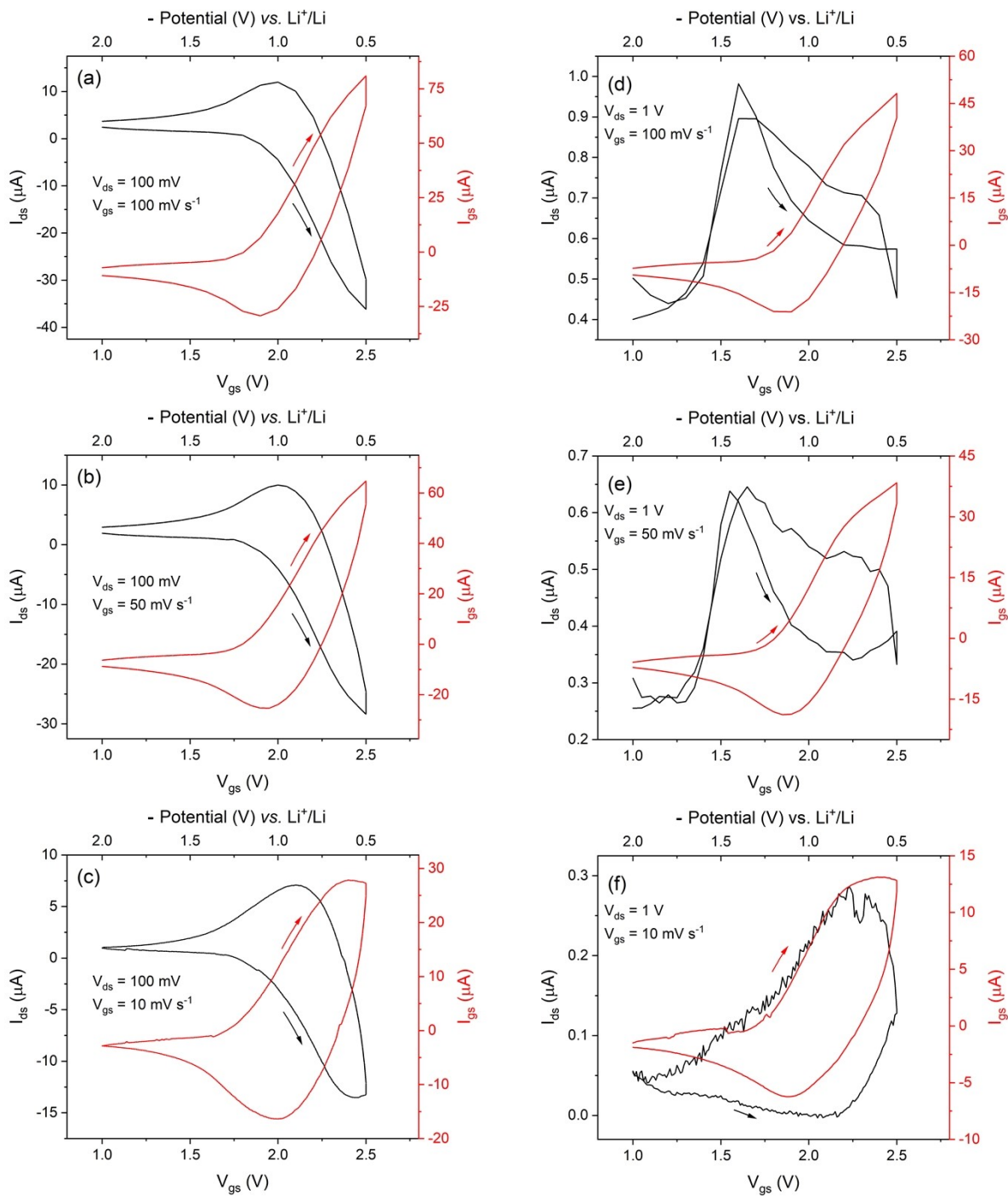
**Fig. S1** LTO, LTO+C, and  $\text{TiO}_2$  based IGTs gated with  $[\text{EMIM}][\text{TFSI}]$  and  $\text{LiTFSI}/[\text{EMIM}][\text{TFSI}]$ . Steps for the device fabrication and assembly, and electrical circuit.



**Fig. S2** X-ray diffraction pattern for (a)  $\text{TiO}_2$  P25, (b) LTO, and (c) LTO+C on Au patterned  $\text{SiO}_2/\text{Si}$  substrate. Insertion: reference number for the identified phases according to the Joint Committee on Powder Diffraction Standards (JCPDS) database.

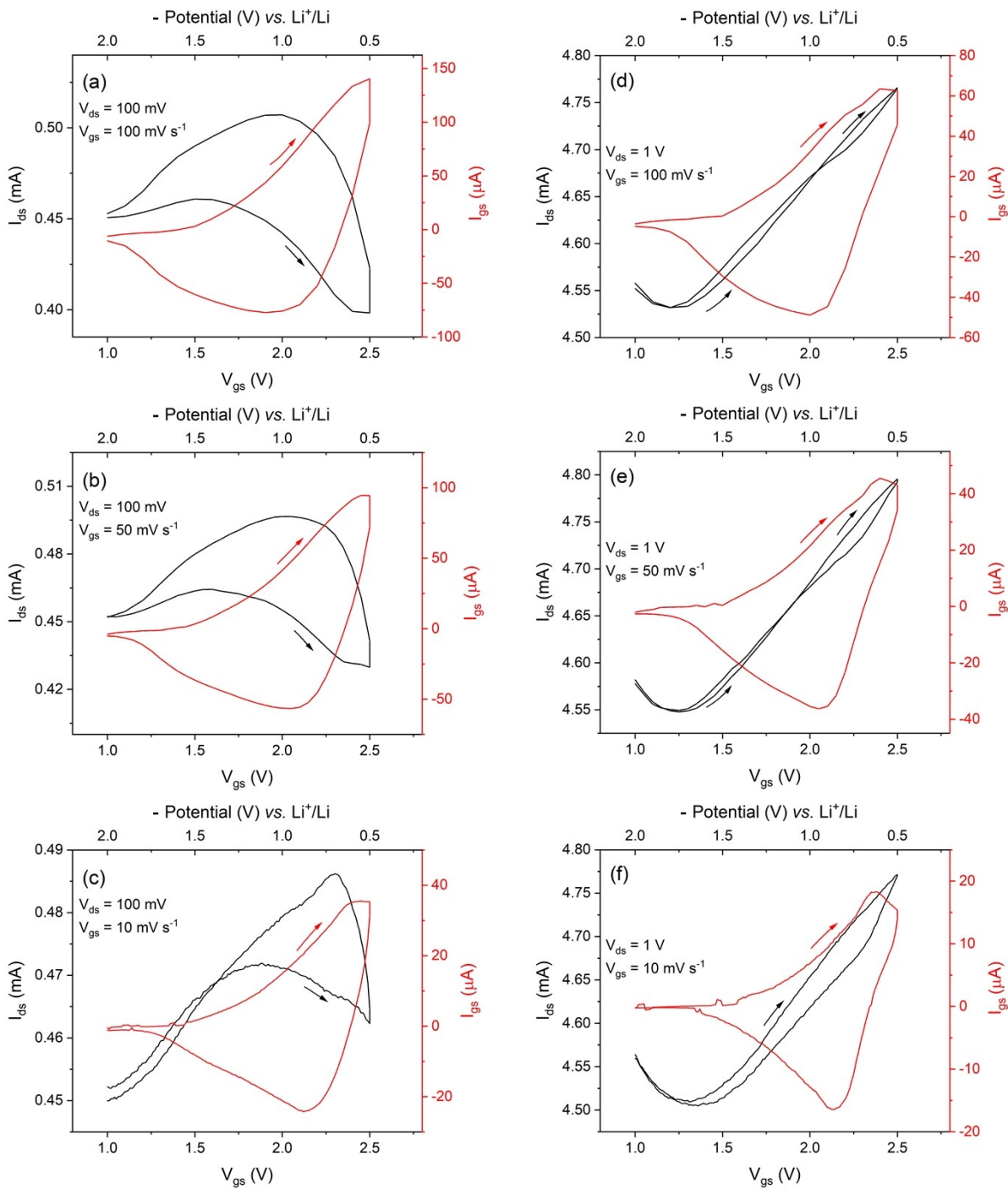


**Fig. S3** Cyclic voltammograms at three sweeping rates of (a) LTO, (b) LTO+C in IGT configuration. 0.1 mol L<sup>-1</sup> LiTFSI in [EMIM][TFSI] as gating medium.



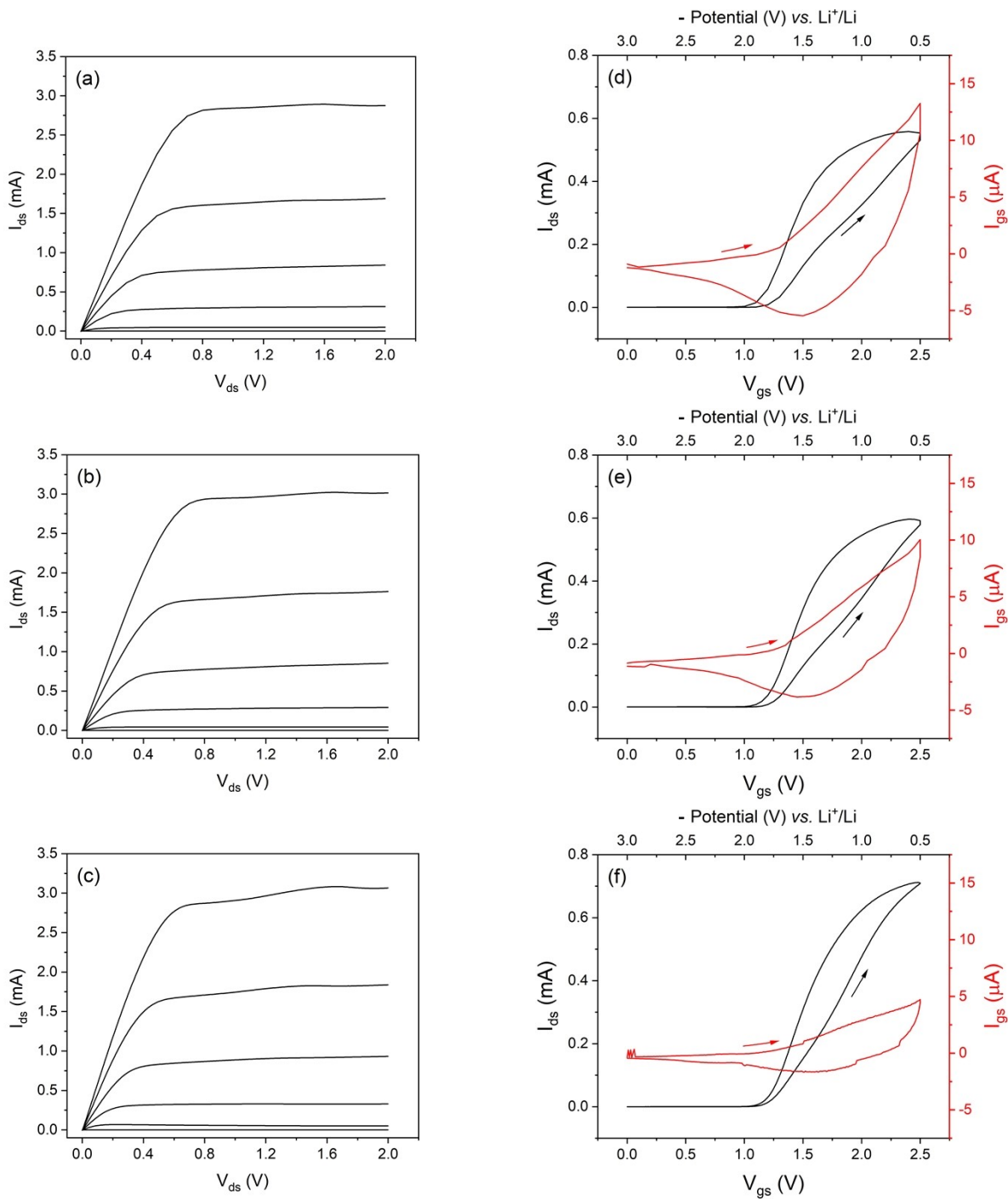
**Fig. S4** Transfer characteristics of LTO with  $V_{ds} = 0.1$  V at three  $V_{gs}$  sweeping rates, (a) 100, (b) 50, and (c) 10  $mV s^{-1}$ . Additionally, with  $V_{ds}=1V$  and three  $V_{gs}$  sweeping rates (d) 100  $mV s^{-1}$ , (e) 50  $mV s^{-1}$ , (f) 10  $mV s^{-1}$ . 0.1  $mol L^{-1}$  LiTFSI in [EMIM][TFSI] as gating medium.

For the  $V_{gs}$  sweeping rates investigated here, there is no clear transistor effect for LTO IGTs, most likely for kinetic reasons: at 10, 50, 100  $mV s^{-1}$ , ions do not have the time needed to suitably redistribute to cause effective doping.

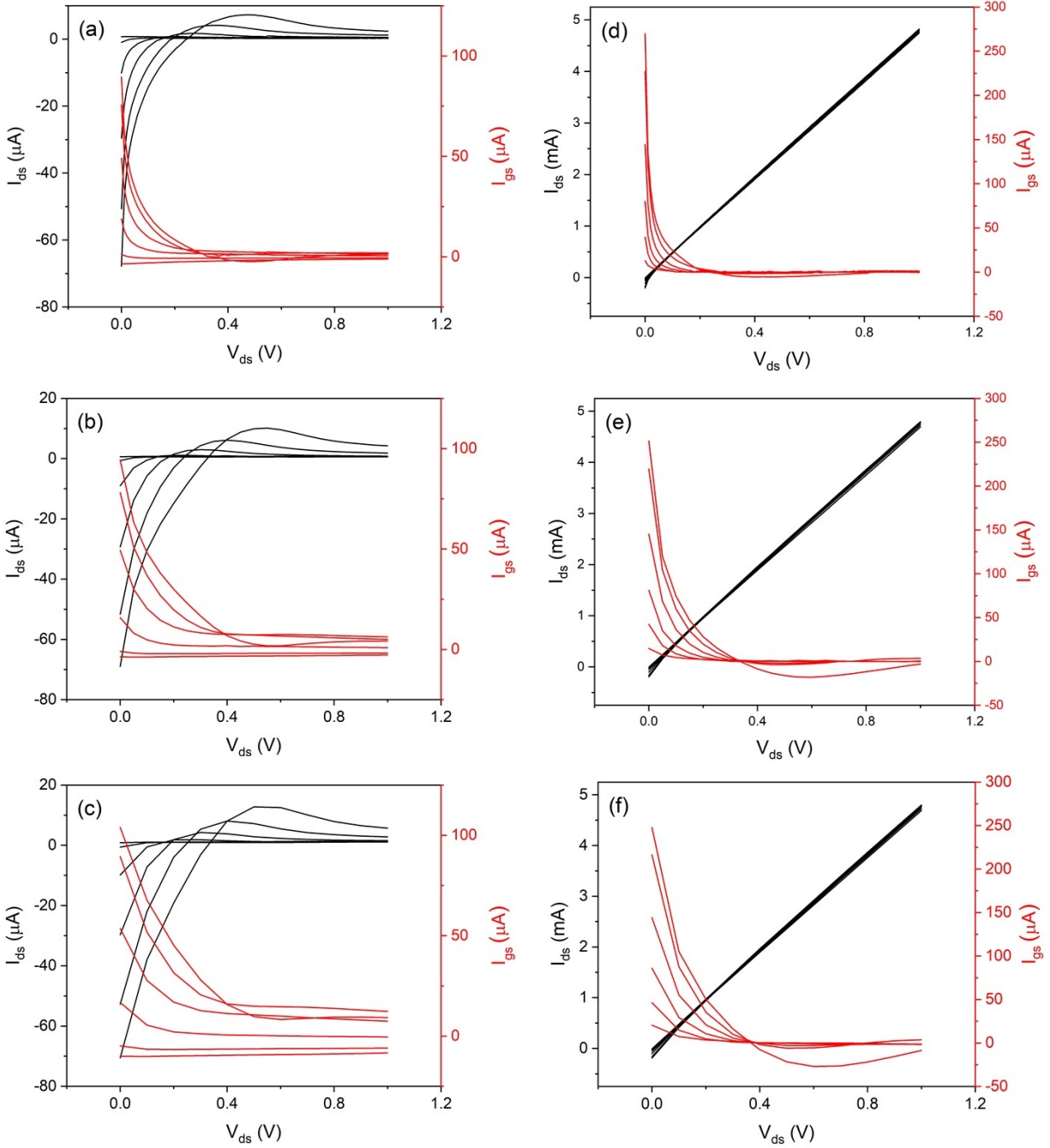


**Fig. S5** Transfer characteristics of LTO+C with  $V_{ds} = 0.1 \text{ V}$  at three  $V_{gs}$  sweeping rates, (a)  $100 \text{ mV s}^{-1}$ , (b)  $50 \text{ mV s}^{-1}$  and (c)  $10 \text{ mV s}^{-1}$ . Additionally, with  $V_{ds}=1\text{V}$  and three  $V_{gs}$  sweeping rates (d)  $100 \text{ mV s}^{-1}$ , (e)  $50 \text{ mV s}^{-1}$ , (f)  $10 \text{ mV s}^{-1}$ .  $0.1 \text{ mol L}^{-1}$  LiTFSI in [EMIM][TFSI] as gating medium.

The results show that at  $V_{ds}=0.1 \text{ V}$  the doping of the LTO+C channel transistor is not clear; higher  $V_{ds}$  values have to be applied to observe a significant doping.



**Fig. S6**  $\text{TiO}_2$  IGTs without  $\text{Li}^+$  in [EMIM][TFSI]. Output characteristics at  $V_{ds}$  sweeping rate of (a)  $100 \text{ mV s}^{-1}$ , (b)  $50 \text{ mV s}^{-1}$ , (c)  $10 \text{ mV s}^{-1}$ ,  $V_{gs}$  from 1 V to 2 V with 200 mV step. Transfer characteristics at  $100 \text{ mV s}^{-1}$ ,  $50 \text{ mV s}^{-1}$ ,  $10 \text{ mV s}^{-1}$  (d, e, f),  $V_{ds}=100 \text{ mV}$ . Potential range  $0 \text{ V} \leq V_{gs} \leq 2.5 \text{ V}$ .



**Fig. S7** Output characteristics of LTO at  $V_{ds}$  scan rate of  $10 \text{ mV s}^{-1}$  (a),  $50 \text{ mV s}^{-1}$  (b),  $100 \text{ mV s}^{-1}$  (c). Output characteristics of LTO+C at  $V_{ds}$  scan rate of  $10 \text{ mV s}^{-1}$  (d),  $50 \text{ mV s}^{-1}$  (e),  $100 \text{ mV s}^{-1}$  (f).  $V_{gs}$  from 1.5 V to 2.5 V with 0.2 V increment.

In the absence of carbon conductive additive, capacitive currents dramatically affect the output characteristics in LTO IGTs. In the presence of carbon conductive additive, the additive determines the shapes of the output characteristics of LTO+C transistors (that feature a clear ohmic behavior).



**TiO<sub>2</sub>**  
**10 mV s<sup>-1</sup>**  
without Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2.5 V	7×10 <sup>-4</sup> A	backward	7×10 <sup>4</sup>
off	0.9 V	1×10 <sup>-8</sup> A	forward	

with Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2 V	8×10 <sup>-4</sup> A	forward	ca 10 <sup>4</sup>
off	0.8 V	5×10 <sup>-8</sup> A	forward	

**50 mV s<sup>-1</sup>**  
without Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2.4 V	6×10 <sup>-4</sup> A	backward	3×10 <sup>4</sup>
off	1 V	2×10 <sup>-8</sup> A	forward	

with Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2 V	8×10 <sup>-4</sup> A	forward	3×10 <sup>3</sup>
off	0.7	3×10 <sup>-7</sup> A	forward	

**100 mV s<sup>-1</sup>**  
without Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2.4 V	6×10 <sup>-4</sup> A	backward	6×10 <sup>3</sup>
off	0.9 V	1×10 <sup>-7</sup> A	forward	

with Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2.5 V	8×10 <sup>-4</sup> A	forward	2×10 <sup>3</sup>
off	0.9 V	4×10 <sup>-7</sup> A	forward	

**LTO**  
**1 mV s<sup>-1</sup>**  
with Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2.5 V	7×10 <sup>-7</sup> A	backward	1.7×10 <sup>2</sup>
off	1.8 V	4×10 <sup>-9</sup> A	forward	

**LTO with CARBON**  
**1 mV s<sup>-1</sup>**  
with Li<sup>+</sup>

	V <sub>gs</sub>	I <sub>ds</sub>	scan	on/off
on	2.5 V	4.7×10 <sup>-3</sup> A	backward	1.06
off	1.5 V	4.5×10 <sup>-3</sup> A	forward	

**Table S1.** Highest values of **on/off** for the IGTs investigated in this work calculated from the transfer characteristics in Figure 2 and Figure 4. The values of on/off depend on the specific transistor channel material (TiO<sub>2</sub>, LTO, LTO+C), on the sweeping rate of V<sub>gs</sub>, and the type of loop (clockwise or anticlockwise) featured by the I<sub>ds</sub> vs. V<sub>gs</sub> transfer characteristics.